

Roll No.:.....

National Institute of Technology, Durgam

Name of the Examination: B. Tech

Branch : ECE Semester : III
Title of the Course : Electronic Devices and Circuits - I Course Code : EC 201

Time: 3 Hours

Maximum Marks: 50

Note:

- Questions are printed on BOTH sides. Answers should be CLEAR AND TO THE POINT.
- All parts of a single question must be answered together. ELSE QUESTION SHALL NOT BE EVALUATED.

Use following data if not given in a problem: $\epsilon_0 = 8.85 \times 10^{-14} \text{ F/cm}$, $\epsilon_r (\text{SiO}_2) = 3.9$, $\epsilon_r (\text{Si}) = 11.8$, At room temperature for Si [$\mu_n = 1350 \text{ cm}^2/\text{V}\cdot\text{S}$, $\mu_p = 480 \text{ cm}^2/\text{V}\cdot\text{S}$, $n_i = 1.5 \times 10^{10}/\text{cm}^3$, $E_g = 1.12 \text{ eV}$], $k = 8.62 \times 10^{-5} \text{ eV/K}$, $\tau_n = \tau_p = 1 \mu\text{s}$, $E_g(\text{Ge}) = 0.7 \text{ eV}$, $n_i(\text{Ge}) = 2.5 \times 10^{13}/\text{cm}^3$.

1. Comment on the following with brief and to the point logical explanation: [1+1+1+2]
 - (a) Variation of band gap with doping.
 - (b) Variation of band gap with temperature.
 - (c) Variation of lattice controlled mobility with temp.
 - (d) Variation of intrinsic carrier concentrations (n_i) with temp and band gap (E_g).
2. Write brief note on followings: [2 * 5 = 10]
 - (a) Thermal Runway
 - (b) Base narrowing effect and early effect
 - (c) Enhancement mode MOSFET
 - (d) p-i-n diode
 - (e) Hall effect
3. A metal-semiconductor (MS) junction is made between a metal of work function $\phi_m = 4.6 \text{ eV}$ and a p-type Si doped with $1.5 \times 10^{14}/\text{cm}^3$ at room temp. Sketch and label the energy band diagrams across the MS junction before contact and after contact. [$\chi_{\text{Si}} = 4.05 \text{ eV}$]. [2.5 + 2.5]
4. Consider a Ge crystal at room temperature doped with $5 \times 10^{17}/\text{cm}^3$ As atoms. Find [5]
equilibrium electron, hole concentrations and position of the Fermi level w.r.t intrinsic energy level (E_i) and conduction energy band (E_c). Draw the energy band diagram also.
5. For a Si bar having length $4 \mu\text{m}$, doped n-type at $10^{17}/\text{cm}^3$. Calculate the current for an [5]
applied voltage of 2 V having a cross sectional area of 0.01 cm^2 . If the voltage is now raised at 100 V what will be the change in current? Electron and hole mobility are $1350 \text{ cm}^2/\text{V}\cdot\text{sec}$ and $400 \text{ cm}^2/\text{V}\cdot\text{sec}$ for low electric field. For higher field, saturation velocity for electron is $V_s = 10^7 \text{ cm/sec}$.

6. Consider a Si sample kept at room temperature having band gap $E_g = 1.12$ eV. [5]

(a) If the Fermi level E_F , is located exactly at the middle of the band gap for this sample, then what will be the probability of finding an electron at $E = E_c + 2KT$.

(b) If the Fermi level E_F , is located such that $E_F = E_v$, then what will be the probability of finding an electron at $E = E_v + KT$.

Note: Put "Tick (✓)" Marks on the write option wherever applicable (Bold) / Fill in the blanks.

7. (a) In an *npn* Si/Si_{1-x}Ge_x heterojunction bipolar transistor (HBT), base is **heavily/ lightly** [2]
doped and increases the **hole/ electron** injection efficiency.

(b) Body or substrate bias effect **increases/ decreases** the current in MOSFETs and [2]
Boron ion implantation **increases/ decreases** the threshold voltage (V_T) in n-channel MOSFETs.

(c) Usually in MOS scaling, the oxide layer thickness **increases/ decreases** and gate [2]
capacitance of the device **increases/ decreases**.

(d) Substrate leakage current in n-MOS devices are due to secondary **electrons/ holes** [2]
and this current **increases/ reduces** at higher gate voltage.

(e) Avalanche breakdown voltage **increases/ decreases** as band gap of the [2]
semiconductor increases and this voltage **increases/ decreases** as doping of the lighter region decreases.

(f) The probability of finding an electron at an energy level $4kT$ above the Fermi level [2]
would be 0.0183 and number of electrons would be $0.0183 \times 10^{19} / \text{cm}^3$ if the density of states is $10^{19} / \text{cm}^3$.

(g) For a Si at a given temperature it is found that 1×10^{10} electrons/ cm^3 have moved from [3]
valance band (VB) to conduction band (CB) when density of atoms is $10^{22} / \text{cm}^3$. Then number of holes in the VB would be 10^{10} and this will be a factor of value 10^{-11} of the total available electrons in the VB.

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Useful Equations

Fermi-Dirac e^- distribution: $f(E) = \frac{1}{e^{(E - E_F)/kT} + 1} \approx e^{-(E - E_F)/kT}$ for $E \gg E_F$.

Equilibrium: $n_0 = \int_{E_c}^{\infty} f(E)N(E)dE = N_c f(E_c) = N_c e^{-(E_c - E_F)/kT}$

$$N_c = 2 \left(\frac{2\pi m_n^* kT}{h^2} \right)^{3/2} \quad N_v = 2 \left(\frac{2\pi m_p^* kT}{h^2} \right)^{3/2} \quad \begin{aligned} n_0 &= n_i e^{(E_F - E_c)/kT} \\ p_0 &= n_i e^{(E_v - E_F)/kT} \end{aligned} \quad n_0 p_0 = n_i^2$$

$$p_0 = N_v [1 - f(E_v)] = N_v e^{-(E_F - E_v)/kT}$$

$$n_i = N_c e^{-(E_c - E_F)/kT}, \quad p_i = N_v e^{-(E_F - E_v)/kT} \quad n_i = \sqrt{N_c N_v} e^{-E_g/2kT} = 2 \left(\frac{2\pi kT}{h^2} \right)^{3/2} (m_n^* m_p^*)^{3/4} e^{-E_g/2kT}$$

$$n = N_c e^{-(E_c - F)/kT} = n_i e^{(F - E_c)/kT}$$

$$p = N_v e^{-(F - E_v)/kT} = n_i e^{(E_v - F)/kT}$$

$$np = n_i^2 e^{(F_n - F_p)/kT}$$

$$\frac{d\mathcal{E}(x)}{dx} = -\frac{d^2V(x)}{dx^2} = \frac{\rho(x)}{\epsilon} = \frac{q}{\epsilon} (p - n + N_d^+ - N_a^-) \quad \mathcal{E}(x) = -\frac{dV(x)}{dx} = \frac{1}{q} \frac{dE_i}{dx}$$

$$\frac{I_x}{A} = J_x = q(n\mu_n + p\mu_p)\mathcal{E}_x = \sigma\mathcal{E}_x$$

Diffusion length: $L = \sqrt{D\tau}$ Einstein relation: $\frac{D}{\mu} = \frac{kT}{q}$

Continuity: $\frac{\partial p(x, t)}{\partial t} = \frac{\partial \delta p}{\partial t} = -\frac{1}{q} \frac{\partial J_p}{\partial x} - \frac{\delta p}{\tau_p} \quad \frac{\partial \delta n}{\partial t} = \frac{1}{q} \frac{\partial J_n}{\partial x} - \frac{\delta n}{\tau_n}$

For steady state diffusion: $\frac{d^2 \delta n}{dx^2} = \frac{\delta n}{D_n \tau_n} = \frac{\delta n}{L_n^2} \quad \frac{d^2 \delta p}{dx^2} = \frac{\delta p}{L_p^2}$

Equilibrium: $V_0 = \frac{kT}{q} \ln \frac{p_p}{p_n} = \frac{kT}{q} \ln \frac{N_a}{n_i^2/N_d} = \frac{kT}{q} \ln \frac{N_a N_d}{n_i^2} \quad \frac{p_p}{p_n} = \frac{n_n}{n_p} = e^{qV_0/kT}$

$$W = \left[\frac{2\epsilon(V_0 - V)}{q} \left(\frac{N_a + N_d}{N_a N_d} \right) \right]^{1/2}$$

Junction Depletion: $C_j = \epsilon A \left[\frac{q}{2\epsilon(V_0 - V)} \frac{N_d N_a}{N_d + N_a} \right]^{1/2} = \frac{\epsilon A}{W}$

One-sided abrupt p^+-n : $x_{cli} = \frac{WN_d}{N_a + N_d} = W$

$V_{bi} = \frac{qN_d W^2}{2\epsilon}$

$\Delta p_n = p(x_{n0}) - p_n = p_n(e^{qV/kT} - 1)$

$\delta p(x_n) = \Delta p_n e^{-x_n/L_p} = p_n(e^{qV/kT} - 1)e^{-x_n/L_p}$

Ideal diode: $I = qA\left(\frac{D_p}{L_p}p_n + \frac{D_n}{L_n}n_p\right)(e^{qV/kT} - 1) = I_0(e^{qV/kT} - 1)$

Stored charge

exp. hole dist.: $Q_p = qA \int_0^x \delta p(x_n) dx_n = qA \Delta p_n \int_0^x e^{-x_n/L_p} dx_n = qAL_p \Delta p_n$

$I_p(x_n = 0) = \frac{Q_p}{\tau_p} = qA \frac{L_p}{\tau_p} \Delta p_n = qA \frac{D_p}{L_p} p_n (e^{qV/kT} - 1)$

$I_{Ep} = qA \frac{D_p}{L_p} \left(\Delta p_E \coth \frac{W_b}{L_p} - \Delta p_C \operatorname{csch} \frac{W_b}{L_p} \right)$

$I_C = qA \frac{D_p}{L_p} \left(\Delta p_E \operatorname{csch} \frac{W_b}{L_p} - \Delta p_C \coth \frac{W_b}{L_p} \right)$ Substrate bias: $\Delta V_T = \frac{\sqrt{2\epsilon_s q N_a}}{C_i} (-V_B)^{1/2}$

Oxide: $C_i = \frac{\epsilon_i}{d}$ Depletion: $C_d = \frac{\epsilon_i}{W}$ MOS: $C = \frac{C_i C_d}{C_i + C_d}$

Inversion: $\phi_s(\text{inv.}) = 2\phi_F = 2 \frac{kT}{q} \ln \frac{N_a}{n_i}$ (6-15) $W = \left[\frac{2\epsilon_s \phi_s}{q N_a} \right]^{1/2}$

$Q_d = -qN_d W_m = -2(\epsilon_s q N_a \phi_F)^{1/2}$ (6-32) At V_{FB} : $C_{FB} = \frac{C_i C_{dchye}}{C_i + C_{dchye}}$

$\Delta p_E = p_n (e^{qV_{EB}/kT} - 1)$

$\Delta p_C = p_n (e^{qV_{CB}/kT} - 1)$

$I_B = qA \frac{D_p}{L_p} \left[(\Delta p_E + \Delta p_C) \tanh \frac{W_b}{2L_p} \right]$

$B = \frac{I_C}{I_{Ep}} = \frac{\operatorname{csch} W_b/L_p}{\coth W_b/L_p} = \operatorname{sech} \frac{W_b}{L_p} \approx 1 - \left(\frac{W_b^2}{2L_p^2} \right)$

(Base transport factor)

$\gamma = \frac{I_{Ep}}{I_{En} + I_{Ep}} = \left[1 + \frac{L_p^n n_n \mu_n^p}{L_n^p p_p \mu_p^n} \tanh \frac{W_b}{L_p} \right]^{-1} \approx \left[1 + \frac{W_b n_n \mu_n^p}{L_n^p p_p \mu_p^n} \right]^{-1}$

(Emitter injection efficiency)

$\frac{i_C}{i_E} = B\gamma = \alpha$ (7-3)

$\frac{i_C}{i_B} = \frac{B\gamma}{1 - B\gamma} = \frac{\alpha}{1 - \alpha} = \beta$ $\frac{i_C}{i_B} = \beta = \frac{\tau_p}{\tau_n}$

(Common base gain)

(Common emitter gain)

(For $\gamma = 1$)